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| A picture containing computer  Description automatically generated(a) | A picture containing text  Description automatically generated(b) |
| A picture containing indoor, sitting, small, counter  Description automatically generated(c) | A picture containing indoor, sitting, small, mirror  Description automatically generated(d) |
| A picture containing text  Description automatically generated(e) | Diagram  Description automatically generated(f) |
| A rocket in the sky  Description automatically generated with low confidence(g) | A close up of a logo  Description automatically generated(h) |

Suppl. Figure 1. APT sample preparation for Preston sample, showing liftout process and typical sample sharpening using Xe plasma FIB. Images show the following: (a) Liftout location, (b) protective W deposition, (c) trench cuts around ROI, (d) cantilever sample prior to liftout, (e) extraction using micro-manipulator, (f) sample mounted on Si micropost, (g) sample during annular milling, (h) sample after final sharpening.